METHOD OF PROCESSING SUBSTRATE, METHOD OF MANUFACTURING SEMICONDUCTOR DEVICE, PROGRAM, AND SUBSTRATE PROCESSING APPARATUS

ABSTRACT

There is provided a technique that includes: (a) supplying a precursor to a substrate; (b) supplying a reactant to the substrate; (c) supplying a regulating agent, which regulates an amount of at least one selected from the group of a molecule of the precursor and a molecule of the reactant adsorbed on the substrate, to the substrate; (d) performing a process in which at least one selected from the group of (a) and (b) overlaps (c); and (e) after (d), performing (a) or (b) which overlaps (c) in (d), independently of (c).

Fig. 1